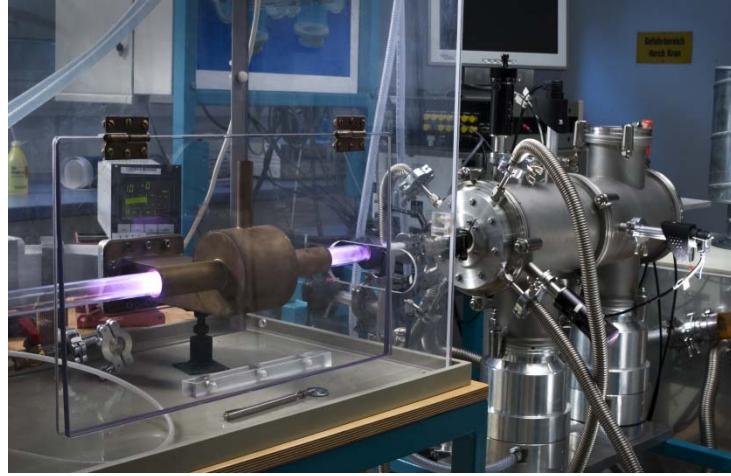


Chemical model of Ar/O₂ microwave plasma with nanoparticle formation from metal precursors

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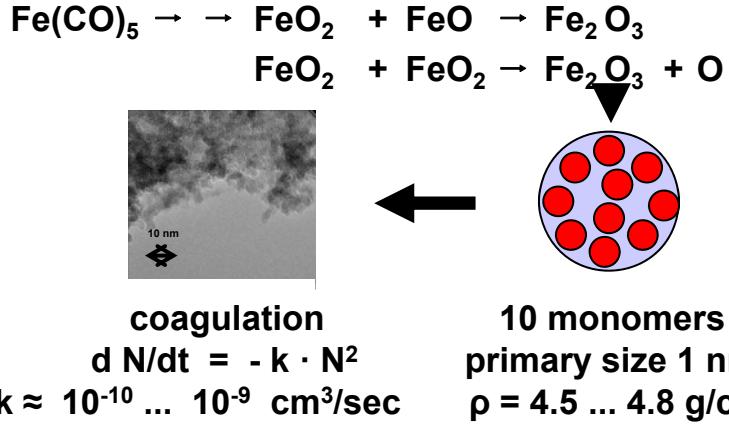
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Flow tube with microwave plasma and particle mass spectrometer

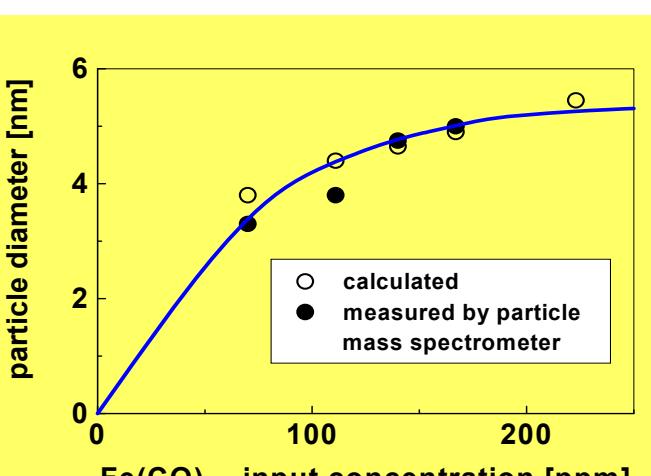
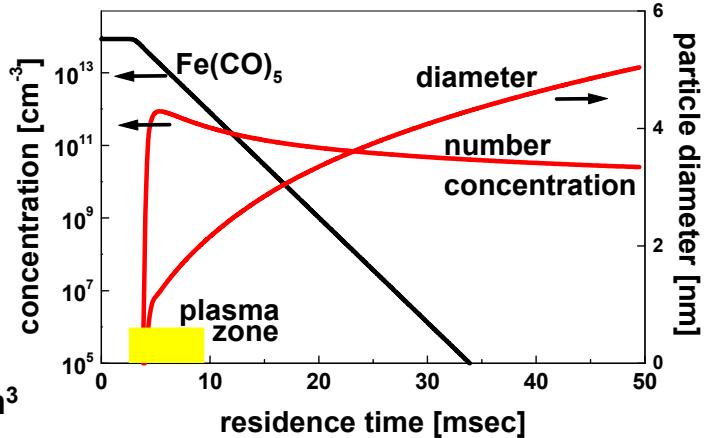
Reactions in the Ar/O₂ – system

ionization	$\text{Ar} + \text{e}^- \rightarrow \text{Ar}^+ + 2\text{e}^-$
attachment	$\text{O}_2 + \text{e}^- + \text{M} \rightarrow \text{O}_2^- + \text{M}$
charge transfer	$\text{Ar}^+ + \text{O}_2 \rightarrow \text{O}_2^+ + \text{Ar}$
recombination	$\text{O}_2^+ + \text{O}_2^- \rightarrow \text{O}_2 + 2\text{O}$
electr. excitation	$\text{Ar} + \text{e}^- \rightarrow \text{Ar}^m + \text{e}^-$
quenching	$\text{Ar}^m + \text{M} \rightarrow \text{Ar} + \text{M}$
reactions of neutral species	$\text{O}_2 + \text{O} + \text{M} \rightarrow \text{O}_3 + \text{M}$
neutral species	$\text{O}_3 + \text{O} \rightarrow 2\text{O}_2$

Mechanism of particle formation



Calculated time profiles



Conclusions

- particle size depends strongly on input concentration and on residence time
- good agreement between model and particle mass spectrometer results
- model is applicable to a wide range of conditions and substances